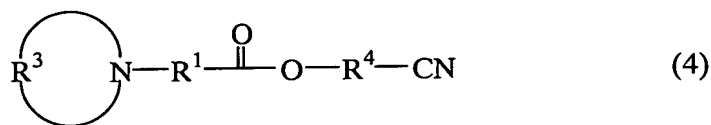
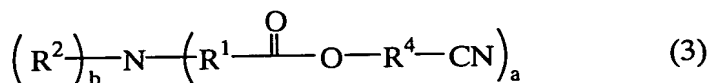
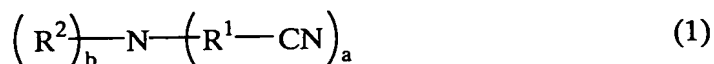


CLAIMS:

1. An amine compound of the following general formula (1), (2), (3) or (4):



wherein R¹ is independently a straight or branched alkylene group of 1 to 4 carbon atoms,

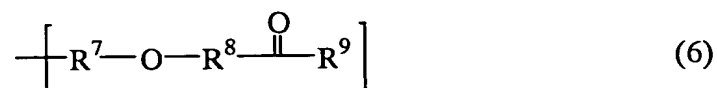
R² is independently hydrogen or a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, carbonyl group, ester group, lactone ring, carbonate or cyano group,

R³ is a straight or branched alkylene group of 2 to 20 carbon atoms which may contain a hydroxy group, ether group, thioether group, carbonyl group, ester group, thioester group or carbonate,

R⁴ is independently a straight or branched alkylene group of 1 to 4 carbon atoms,

"a" is an integer of 1 to 3, and a+b = 3.

2. The amine compound of claim 1 wherein R² in formulae (1) and (3) has the following general formula (5), (6), (7) or (8):



5 wherein R⁵, R⁷ and R¹⁰ each are a straight or branched alkylene group of 1 to 4 carbon atoms,

R⁶ and R⁹ each are hydrogen or a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, ester group, lactone ring or
10 cyano group,

R⁵ and R⁶, taken together, may form a ring with the oxygen atom,

R⁸ is a single bond or a straight or branched alkylene group of 1 to 4 carbon atoms,

15 R¹¹ is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, ester group or lactone ring,

R¹² is a (n+1)-valent straight or branched organic group of 1 to 4 carbon atoms,

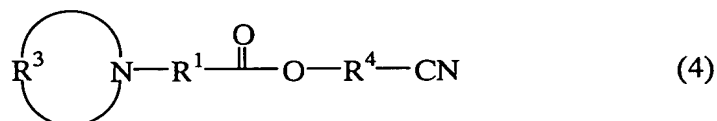
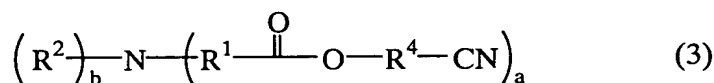
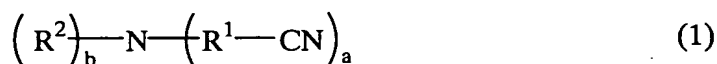
20 R¹³ is independently a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms which may contain an ether group, ester group, hydroxy group, lactone ring, cyano group or carbonyl group,

25 R¹² and R¹³ or two R¹³ groups, taken together, may form a ring with the oxygen atom or the oxygen atom and a carbon atom in R¹², and

n is equal to 2, 3 or 4.

3. A resist composition comprising a basic compound having a cyano group.

4. The resist composition of claim 3 comprising as the basic compound having a cyano group at least one of amine compounds of the following general formulae (1), (2), (3) and (4):



wherein R¹ is independently a straight or branched alkylene group of 1 to 4 carbon atoms,

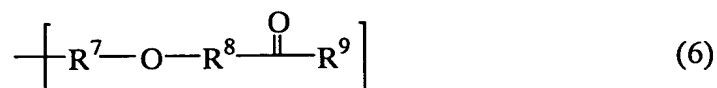
R² is independently hydrogen or a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, carbonyl group, ester group, lactone ring, carbonate or cyano group,

R³ is a straight or branched alkylene group of 2 to 20 carbon atoms which may contain a hydroxy group, ether group, thioether group, carbonyl group, ester group, thioester group or carbonate,

R⁴ is independently a straight or branched alkylene group of 1 to 4 carbon atoms,

"a" is an integer of 1 to 3, and a+b = 3.

5. The resist composition of claim 4 wherein R² in formulae (1) and (3) has the following general formula (5), (6), (7) or (8):



5 wherein R⁵, R⁷ and R¹⁰ each are a straight or branched alkylene group of 1 to 4 carbon atoms,

R⁶ and R⁹ each are hydrogen or a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, ester group, lactone ring or cyano group,

R⁵ and R⁶, taken together, may form a ring with the oxygen atom,

R⁸ is a single bond or a straight or branched alkylene group of 1 to 4 carbon atoms,

15 R¹¹ is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, ester group or lactone ring,

R¹² is a (n+1)-valent straight or branched organic group of 1 to 4 carbon atoms,

20 R¹³ is independently a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms which may contain an ether group, ester group, hydroxy group, lactone ring, cyano group or carbonyl group,

25 R¹² and R¹³ or two R¹³ groups, taken together, may form a ring with the oxygen atom or the oxygen atom and a carbon atom in R¹², and

n is equal to 2, 3 or 4.

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6. A positive resist composition comprising
(A) the amine compound of claim 1,
(B) an organic solvent,
(C) a base resin having an acidic functional group
5 protected with an acid labile group, which is normally
alkali insoluble or substantially alkali insoluble, but
becomes alkali soluble upon elimination of the acid labile
group, and
(D) a photoacid generator.

7. The positive resist composition of claim 6 further
comprising (E) a dissolution inhibitor.

8. A negative resist composition comprising
(A) the amine compound of claim 1,
(B) an organic solvent,
(C) a base resin which is normally alkali soluble, but
becomes substantially alkali insoluble when crosslinked with
a crosslinker,
(D) a photoacid generator, and
(F) the crosslinker capable of crosslinking under the
action of acid.

9. A process for forming a resist pattern comprising the
steps of:

applying the resist composition of claim 6 onto a
substrate to form a coating,

heat treating the coating and then exposing it to
high-energy radiation having a wavelength of less than 300
nm or electron beams through a photo mask, and

optionally heat treating the exposed coating and
developing it with a developer.